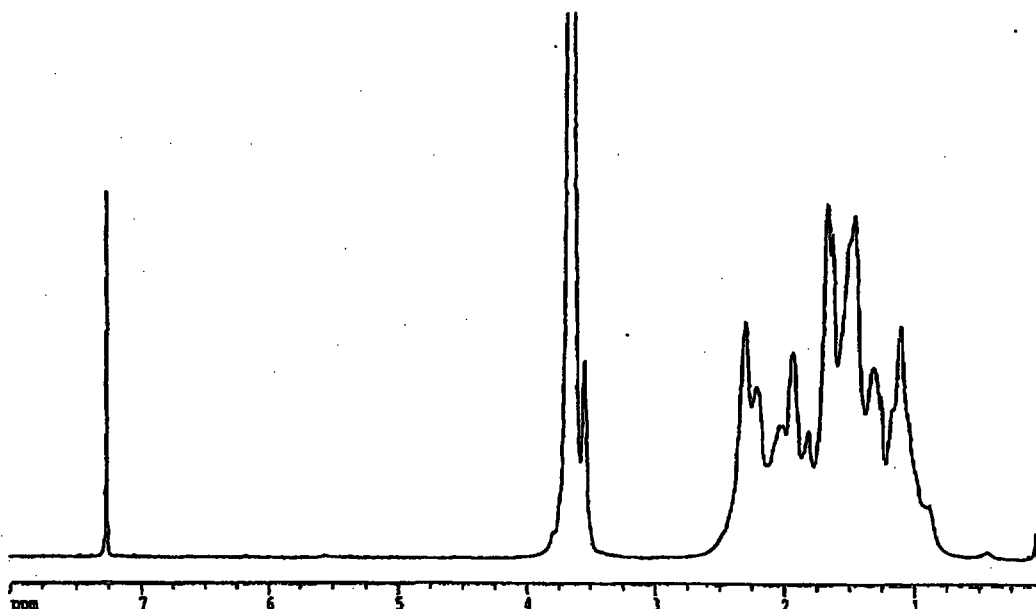




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(54) Title: POLYCYCLIC COPOLYMER COMPOSITIONS



(57) Abstract

Copolymers containing repeating units polymerized from at least one polycyclic monomer and at least one acrylic monomer are disclosed. The copolymer is formed by addition polymerization in the presence of a Group VIII transition metal catalyst. The copolymers contain hydrocarbyl and/or functional substituents pendant from the polymer backbone. In one embodiment the copolymer contains pendant ester substituents containing acid labile groups. The copolymers are useful as resist materials that are sensitive to imaging radiation.